# INTEL FIRST TO DEMONSTRATE WORKING 45 nm CHIPS

New Technology Will Improve Energy Efficiency and Boost Capabilities of Future Intel Platforms

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# 65 nm Status

- Announced shipping 65nm for revenue in Oct. 2005
- Two 65nm/300mm fabs shipping in volume (D1D and Fab 12); with two more coming in 2006
- Intel has shipped more than a million dualcore processors made on 65nm process technology
- CPU shipment cross-over from 90nm to 65nm projected for Q3/06



# What are We Announcing Today?

- Intel is first to reach an important milestone in the development of 45 nm logic technology
- Fully functional 153 Mbit SRAM chips have been made with >1 billion transistors each
- The memory cell size on these SRAM chips is 0.346  $\mu m^2,$  almost half the size of the 65 nm cell
- This milestone demonstrates that Intel is on track for delivery of its 45 nm logic technology in 2H 2007



# 45 nm Technology Benefits

Compared to today's 65 nm technology, the 45 nm technology will provide the following product benefits:

~2x improvement in transistor density, for either smaller chip size or increased transistor count

>20% improvement in transistor switching speed or >5x reduction in leakage power

>30% reduction in transistor switching power

This process technology will provide the foundation to deliver improved performance/Watt that will enhance the user experience



# Intel's Logic Technology Evolution

Process Name	<u>P1262</u>	<u>P1264</u>	<u>P1266</u>	<u>P1268</u>
Lithography	90 nm	65 nm	45 nm	32 nm
1 <sup>st</sup> Production	2003	2005	2007	2009

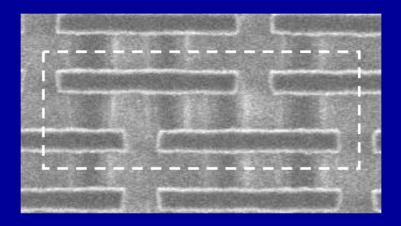
#### Moore's Law continues!

Intel continues to develop a new technology generation every 2 years

P1266 is being developed by the Logic Technology Development group located in Hillsboro, Oregon



### 45 nm SRAM Cell

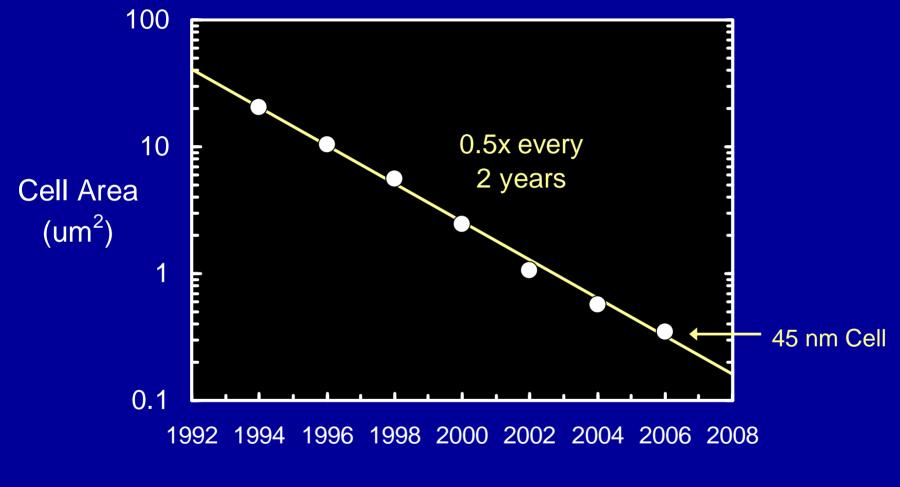


#### 6-transistor SRAM cell area of 0.346 $\mu$ m<sup>2</sup>

193 nm dry lithography used to pattern critical layers



#### Intel SRAM Cell Size Trend

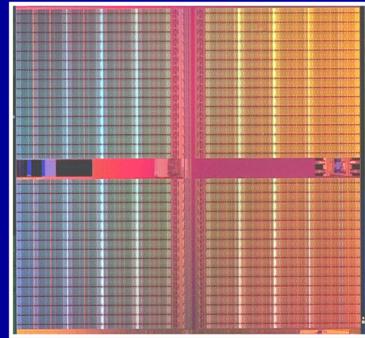


Transistor density continues to double every 2 years



# 45 nm SRAM Chip

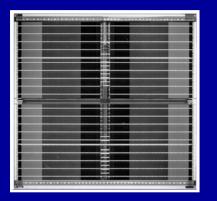
0.346 μm² cell
153 Mbit density
119 mm² chip size
>1 billion transistors
Functional silicon in Jan '06

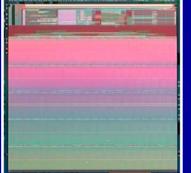


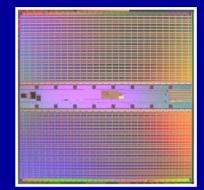
45 nm SRAM test vehicle includes all transistor and interconnect features to be used on 45 nm microprocessors

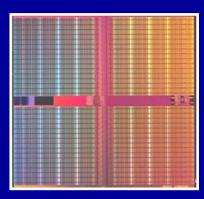


# Intel SRAM Test Chips







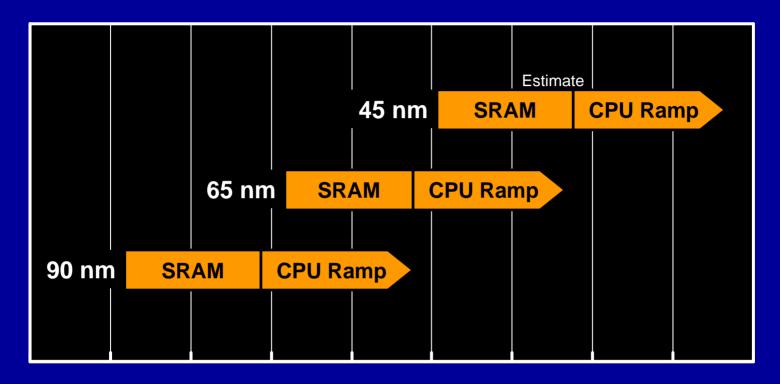


130 nm Process	90 nm Process	65 nm Process	45 nm Process
2.45 $\mu$ m <sup>2</sup> cell	1.0 μm <sup>2</sup> cell	$0.57 \ \mu m^2 \ cell$	0.346 μm² cell
18 Mbit	50 Mbit	70 Mbit	153 Mbit
103 mm <sup>2</sup>	109 mm <sup>2</sup>	110 mm <sup>2</sup>	119 mm <sup>2</sup>
March '00	February '02	April '04	Januarv '06

New SRAM test vehicle developed every 2 years to lead development of logic technologies



# Logic Technology Schedules

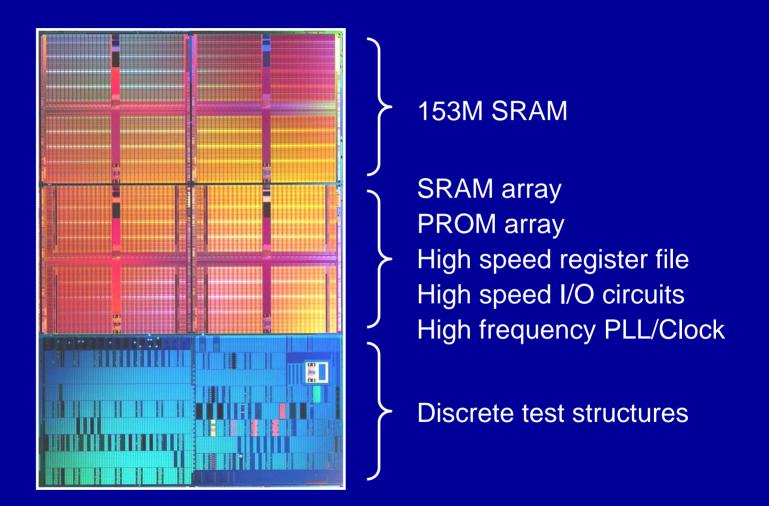


2001 2002 2003 2004 2005 2006 2007 2008 2009 2010

SRAM test vehicles are used to demonstrate technology performance, yield and reliability prior to CPU product ramp



# 45 nm Shuttle Test Chip



45 nm shuttle test chip includes SRAM and logic circuits for CPUs



### Summary

- Intel's 45 nm logic technology is being demonstrated on fully functional 153 Mbit SRAM chips with >1 billion transistors
- These SRAM test chips exercise all of the transistor and interconnect features to be used on 45 nm microprocessors
- This 45 nm technology will provide significant density, performance and power improvements over today's 65 nm technology
- No other company has demonstrated this level of progress on its 45 nm process
- Intel's 45 nm logic technology is on track for product shipments in 2H 2007

